Tamas Szorenyi

List of Publications by Year
in descending order

83 papers	1,370 citations	393982 19 h-index	377514 34 g-index
83 all docs	83 docs citations	83 times ranked	1136 citing authors

#	Article	IF	Citations
1	On the electrical resistance of laser joined metal sheets. , 2021, , .		0
2	Characterization of plasma reflectivity response of optical glasses processed by 34 fs pulses: analysis in the context of ablation parameters. , 2021, , .		0
3	The effect of seam geometry on properties of laser welded nickel coated stainless steel stripes. , 2021, , .		0
4	Spectroscopic quantification of the nanoparticle production efficiency of copper wire explosion. Journal of Applied Physics, 2021, 129, 195902.	1.1	2
5	Surface processing of optical glasses with 34 fs pulses: ablation thresholds and crater shape. , 2021, , .		0
6	Processing of optical glasses by single, 34Âfs pulses in the strong field ionization domain: ablation characteristics and crater morphology. Applied Physics A: Materials Science and Processing, 2020, 126, 1.	1.1	3
7	Time integrated transient reflectivity versus ablation characteristics of Borofloat, BK7, and B270 optical glasses ablated by 34 fs pulses. Optical Materials Express, 2020, 10, 549.	1.6	1
8	Laser welding and its implementation in the assembly of battery packs in aviation. International Journal of Sustainable Aviation, 2020, 6, 51.	0.1	0
9	Why do horseflies need polarization vision for host detection? Polarization helps tabanid flies to select sunlit dark host animals from the dark patches of the visual environment. Royal Society Open Science, 2017, 4, 170735.	1.1	27
10	Nonlinear waves generated on liquid silicon layer by femtosecond laser pulses. Applied Surface Science, 2013, 285, 588-599.	3.1	5
11	Multipulse irradiation of silicon by femtosecond laser pulses: Variation of surface morphology. Applied Surface Science, 2012, 258, 3589-3597.	3.1	15
12	Homogeneous films by inverse pulsed laser deposition. Applied Surface Science, 2011, 257, 5324-5327.	3.1	6
13	Si-doped carbon nanostructured films by pulsed laser deposition from a liquid target. Solid State Sciences, 2009, 11, 1783-1787.	1.5	0
14	10Boron distribution measurement in laser ablated B4C thin films using (n,Î±) reaction and LR-115 passive detector. Radiation Measurements, 2009, 44, 795-797.	0.7	4
15	A point source analytical model of inverse pulsed laser deposition. Applied Physics A: Materials Science and Processing, 2008, 93, 691-696.	1.1	4
16	Laser-induced convection nanostructures on SiON/Si interface. Journal of Applied Physics, 2008, 104, .	1.1	3
17	Test particle Monte Carlo study of backward deposition during evaporation into a background gas. Journal Physics D: Applied Physics, 2008, 41, 015303.	1.3	10
18	Ultrashort Pulse PLD: A Technique for Nanofilm Fabrication. NATO Science for Peace and Security Series B: Physics and Biophysics, 2008, , 121-143.	0.2	0

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19	Ablation with femtosecond pulses: The effect of temporal contrast. Applied Surface Science, 2007, 253, 7779-7782.	3.1	5
20	Carbon nitride films of uniform thickness by inverse PLD. Applied Surface Science, 2007, 253, 8197-8200.	3.1	5
21	Atomic force microscopic characterization of films grown by inverse pulsed laser deposition. Applied Surface Science, 2006, 252, 4661-4666.	3.1	7
22	On the orientation independence of inverse pulsed laser deposition. Applied Surface Science, 2006, 252, 4656-4660.	3.1	0
23	Property improvement of pulsed laser deposited boron carbide films by pulse shortening. Applied Surface Science, 2006, 252, 4707-4711.	3.1	10
24	Carbon-Based Materials by Pulsed Laser Deposition. , 2006, , 75-104.		1
25	Thickness distribution of carbon nitride films grown by inverse-pulsed laser deposition. Applied Surface Science, 2005, 247, 182-187.	3.1	24
26	Number density and size distribution of droplets in KrF excimer laser deposited boron carbide films. Applied Surface Science, 2005, 247, 45-50.	3.1	7
27	Thin film growth by inverse pulsed laser deposition. Thin Solid Films, 2005, 484, 165-169.	0.8	10
28	Compositional and thickness distribution of carbon nitride films grown by PLD in the target plane. Thin Solid Films, 2004, 453-454, 172-176.	0.8	21
29	Comparison of growth rate and surface structure of carbon nitride films, pulsed laser deposited in parallel, on axis planes. Thin Solid Films, 2004, 453-454, 431-435.	0.8	16
30	Correlation of compositional and structural changes during pulsed laser deposition of tantalum oxide films. Thin Solid Films, 2004, 453-454, 245-250.	0.8	13
31	A novel PLD configuration for deposition of films of improved quality: a case study of carbon nitride. Applied Physics A: Materials Science and Processing, 2004, 79, 1207-1209.	1.1	7
32	KrF excimer laser processing of thick diamond-like carbon films. Applied Physics A: Materials Science and Processing, 2004, 79, 1373-1376.	1.1	5
33	The combined effect of laser fluence and target deterioration in determining the chemical composition of pulsed laser deposited boron carbide films. Surface and Coatings Technology, 2004, 180-181, 127-131.	2.2	9
34	The chemical structure of carbon nitride films fabricated by pulsed plasma-assisted chemical vapor deposition. Surface and Coatings Technology, 2004, 180-181, 271-274.	2.2	4
35	Structure and composition of carbon-nitride films grown by sub-ps PLD. Applied Surface Science, 2003, 208-209, 547-552.	3.1	10
36	Morphological study of PLD grown carbon films. Applied Surface Science, 2003, 208-209, 566-574.	3.1	13

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37	On the growth mechanism of pulsed laser deposited carbon nitride films. Applied Surface Science, 2003, 208-209, 502-506.	3.1	7
38	Pressure control of properties of pulsed laser deposited carbon and carbon nitride films. Journal of Applied Physics, 2003, 94, 2097-2101.	1.1	11
39	Correlation between surface oxygen content and microstructure of carbon nitride films. Diamond and Related Materials, 2002, 11, 1153-1156.	1.8	10
40	The effect of process parameters on the chemical structure of pulsed laser deposited carbon nitride films. Diamond and Related Materials, 2002, 11, 1157-1160.	1.8	8
41	Morphology and composition of ArF excimer laser deposited carbon nitride films as determined by analytical TEM. Applied Surface Science, 2002, 186, 502-506.	3.1	9
42	Influence of the nitrogen content on the field emission properties of a-CNx films prepared by pulsed laser deposition. Applied Surface Science, 2002, 197-198, 316-320.	3.1	9
43	Characterization of CNx films deposited by pulsed laser ablation using spectroscopic ellipsometry. Surface and Coatings Technology, 2002, 151-152, 144-150.	2.2	10
44	Correlation between hydrogen content and structure of pulsed laser deposited carbon nitride films. Diamond and Related Materials, 2001, 10, 2107-2112.	1.8	13
45	XPS study of pulsed laser depositedCNxfilms. Physical Review B, 2001, 64, .	1.1	145
46	Dependence of nitrogen content and deposition rate on nitrogen pressure and laser parameters in ArF excimer laser deposition of carbon nitride films. Applied Surface Science, 2000, 168, 248-250.	3.1	20
47	Chemical analysis of pulsed laser deposited a-CN films by comparative infrared and X-ray photoelectron spectroscopies. Surface and Coatings Technology, 2000, 125, 308-312.	2.2	62
48	Pulsed laser deposition of carbon nitride films by a sub-ps laser. Applied Physics A: Materials Science and Processing, 2000, 70, 9-11.	1.1	9
49	Pulsed laser deposition of metals at target temperatures close to the melting point. Applied Physics A: Materials Science and Processing, 1999, 69, S617-S619.	1.1	5
50	Chemical analysis of a-CN x thin films synthesized by nanosecond and femtosecond pulsed laser deposition. Applied Physics A: Materials Science and Processing, 1999, 69, S941-S944.	1.1	24
51	Diamond-like carbon layer formation on graphite by excimer laser irradiation. Applied Physics A: Materials Science and Processing, 1998, 66, 659-661.	1.1	20
52	Laser direct writing of tin oxide patterns. Vacuum, 1998, 50, 327-329.	1.6	7
53	Microscopic description of thin film formation in pulsed laser deposition in the presence of a background gas. Applied Surface Science, 1998, 127-129, 703-709.	3.1	6
54	Dependence of the thickness profile of pulsed laser deposited bismuth films on process parameters. Applied Surface Science, 1997, 109-110, 327-330.	3.1	18

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55	Atypical characteristics of KrF excimer laser ablation of indium-tin oxide films. Applied Surface Science, 1995, 86, 219-222.	3.1	41
56	Metal pattern deposition by laser-induced forward transfer. Applied Surface Science, 1995, 86, 196-201.	3.1	35
57	The effect of process parameters on the O/Mo ratio in laser deposition of molybdenum oxides from aqueous solutions. Applied Surface Science, 1995, 86, 500-503.	3.1	1
58	Kinetic model for scanning laser-induced deposition from the liquid phase. Applied Surface Science, 1995, 86, 494-499.	3.1	5
59	Dynamics of longâ€pulse laser transfer of micrometerâ€sized metal patterns as followed by timeâ€resolved measurements of reflectivity and transmittance. Journal of Applied Physics, 1995, 78, 2775-2781.	1.1	33
60	Deposition of amorphous silicon nitride thin films by CO2 laser-induced chemical vapour deposition. Journal of Non-Crystalline Solids, 1995, 187, 353-360.	1.5	5
61	Excimer laser processing of indiumâ€tinâ€oxide films: An optical investigation. Journal of Applied Physics, 1995, 78, 6211-6219.	1.1	210
62	Dynamics of excimer laser ablation of thin tungsten films monitored by ultrafast photography. Applied Physics A: Materials Science and Processing, 1995, 60, 431-436.	1.1	30
63	Laser-induced compound formation and transfer of stacked elemental layers. Thin Solid Films, 1994, 245, 40-43.	0.8	1
64	Dependence of deposition kinetics on precursor concentration and writing speed in pyrolytic laser deposition from solution. Thin Solid Films, 1994, 241, 67-70.	0.8	7
65	Tailoring silicon oxide film properties by tuning the laser beam-to-substrate distance in ArF laser-induced chemical vapor deposition. Thin Solid Films, 1994, 241, 80-83.	0.8	1
66	Deposition of micrometerâ€sized tungsten patterns by laser transfer technique. Applied Physics Letters, 1994, 64, 3506-3508.	1.5	65
67	High speed laser writing of gold lines from organic solutions. Applied Surface Science, 1993, 69, 75-78.	3.1	9
68	Ar+ laser-induced forward transfer (LIFT): a novel method for micrometer-size surface patterning. Applied Surface Science, 1993, 69, 317-320.	3.1	74
69	Quest for high quality local electroless laser deposition from the liquid phase: decomposition of ammonium molybdate. Applied Surface Science, 1993, 69, 326-329.	3.1	8
70	Time resolved reflectivity and transmission measurements during laser induced blow-off of thin metal films. Applied Surface Science, 1993, 69, 330-334.	3.1	20
71	Organic solutions of triphenylphosphine gold complexes: attractive new candidates for gold deposition. Materials Science and Engineering B: Solid-State Materials for Advanced Technology, 1993, 17, 101-103.	1.7	7
72	Gas mixture dependence of the LCVD of SiO2 films using an ArF laser. Applied Surface Science, 1990, 46, 206-209.	3.1	19

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73	Growth kinetics of laser chemical vapor deposited tungsten. Spectrochimica Acta Part A: Molecular Spectroscopy, 1990, 46, 505-508.	0.1	0
74	Pulsed laser ablative deposition of thin metal films. Applied Surface Science, 1989, 36, 157-163.	3.1	58
75	Lateral growth rates in laser CVD of tungsten microstructures. Surface Science, 1988, 202, 442-456.	0.8	10
76	Kr+laserâ€‘induced chemical vapor deposition of W. Journal of Applied Physics, 1987, 62, 673-675.	1.1	35
77	Noise measurements on thin films deposited from vanadium pentoxide gels. Solid State Communications, 1986, 58, 609-611.	0.9	7
78	The role of spin-spin interaction in the electrical conductivity of vanadium phosphate glasses. Journal of Non-Crystalline Solids, 1985, 70, 429-438.	1.5	9
79	Structural characterization of V2O5/P2O5 glasses: density and molar volume data. Journal of Non-Crystalline Solids, 1985, 70, 297-300.	1.5	11
80	Thickness-dependent conductivity of near-stoichiometric V2O5 films deposited from gels. Thin Solid Films, 1984, 121, 29-34.	0.8	9
81	A comparative survey of the evaluation of optical constants of weakly absorbing thin layers. Acta Physica Hungarica, 1984, 55, 241-245.	0.1	1
82	Characterization of amorphous vanadium pentoxide thin films prepared by chemical vapour deposition (CVD) and vacuum deposition. Acta Physica Academiae Scientiarum Hungaricae, 1980, 49, 217-221.	0.1	12
83	Correlation between structure and properties in vanadium phosphate glasses and amorphous V2O5â^'x/O<x>1/ films. Journal of Non-Crystalline Solids, 1980, 42, 393-400.	1.5	7